



# PHILIPS

## Philips Semiconductors

Law Department

a Philips Electronics North America Company

November 9, 1994

811 E. Arques Avenue  
P.O. Box 3409  
Sunnyvale, CA 94088-3409  
Telephone 408/991-2000

Mr. Doug Earp  
City of Albuquerque  
Environmental Health Department  
P.O. Box 1293-87103  
Albuquerque, NM 87103

Re: Old Coronado Landfill

Dear Doug:

As a followup to our conversation yesterday, enclosed please find the following material:

- Monitoring wells completion details, which indicate "screened interval";
- Monitoring wells analytical data, dated January 8, 1993;
- Maps indicating general location of Old Coronado Landfills.

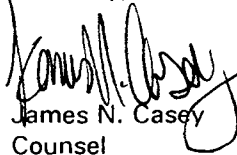
In quarter 1 of 1994 the monitoring wells were tested and analyzed. Unfortunately I do not have the actual test results. However, I have been informed the results indicated non-detects for all constituents, except for Tetrachloroethene. Tetrachloroethene was found in the following reporting levels:

- Well 1 - 9.8 ppb
- Well 2 - 9.0 ppb
- Well 3 - 0 ppb
- Well 4 - 5.4 ppb

With regard to the next sampling event, sampling is not scheduled until the first quarter of 1995.

After you have had an opportunity to review the enclosed, if you have any questions please don't hesitate to contact me.

Sincerely,

  
James N. Casey  
Counsel

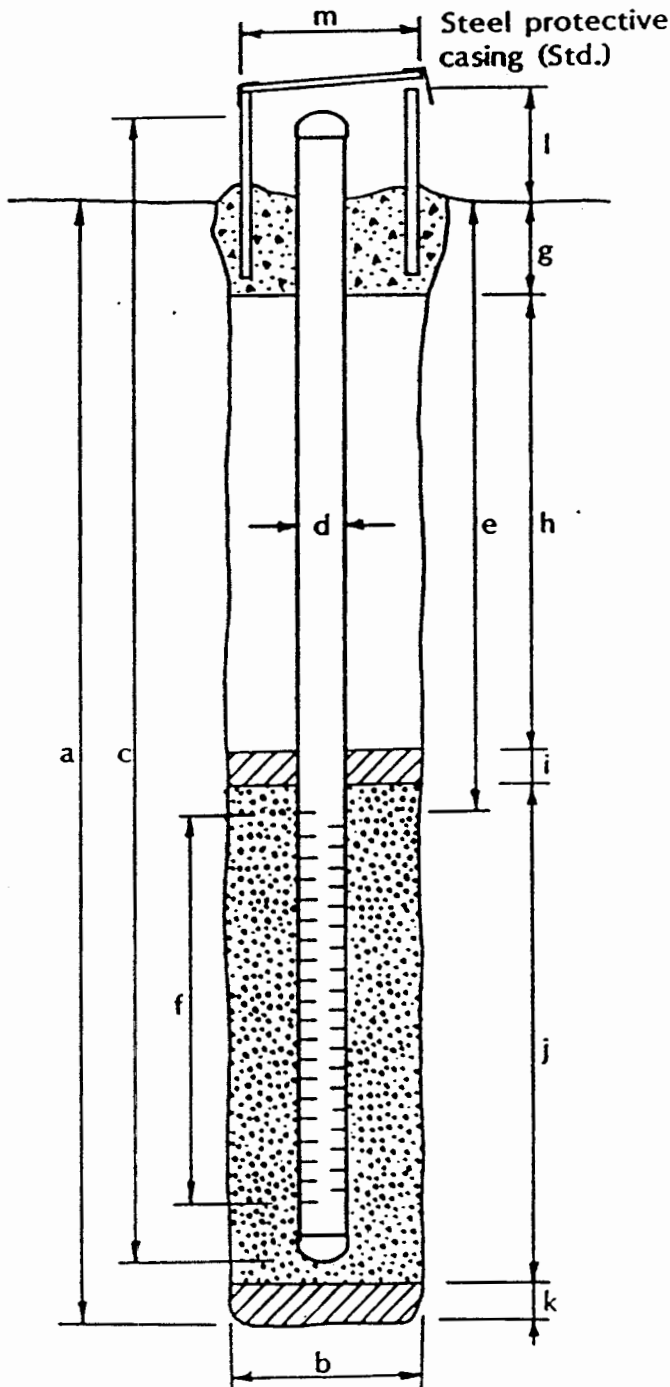
JNC:cb  
Enclosures

# WELL DETAILS



PROJECT NUMBER 377-16.01  
 PROJECT NAME Signetics  
 COUNTY Bernalillo Co., NM  
 WELL PERMIT NO. N/A

BORING / WELL NO. MW-1  
 TOP OF CASING ELEV. 5168.70  
 GROUND SURFACE ELEV. 5168.17  
 DATUM Mean Sea Level



## EXPLORATORY BORING

a. Total depth 247 ft.  
 b. Diameter 7 7/8 in.  
 Drilling method Air/Mud Rotary

## WELL CONSTRUCTION

c. Casing length 230 ft.  
 Material Schedule 40 PVC  
 d. Diameter 2 in.  
 e. Depth to top perforations 199.5 ft.  
 f. Perforated length 30 ft.  
 Perforated interval from 199.5 to 229.5 ft.  
 Perforation type Machine Slotted  
 Perforation size 0.02 inch  
 g. Surface seal 3 ft.  
 Seal material Cement w/ 3% Bentonite  
 h. Backfill 171 ft.  
 Backfill material Cement w/ 3% Bentonite  
 i. Seal 5 ft.  
 Seal material Bentonite  
 j. Gravel pack  $\pm$  68 ft.  
 Pack material CSSI 8x12 Sand  
 k. Bottom seal N/A ft.  
 Seal material N/A  
 l. Casing height \* .5 ft.  
 m. Protective casing diameter 10 in.

$\pm$  includes filter pack

\* top of PVC casing

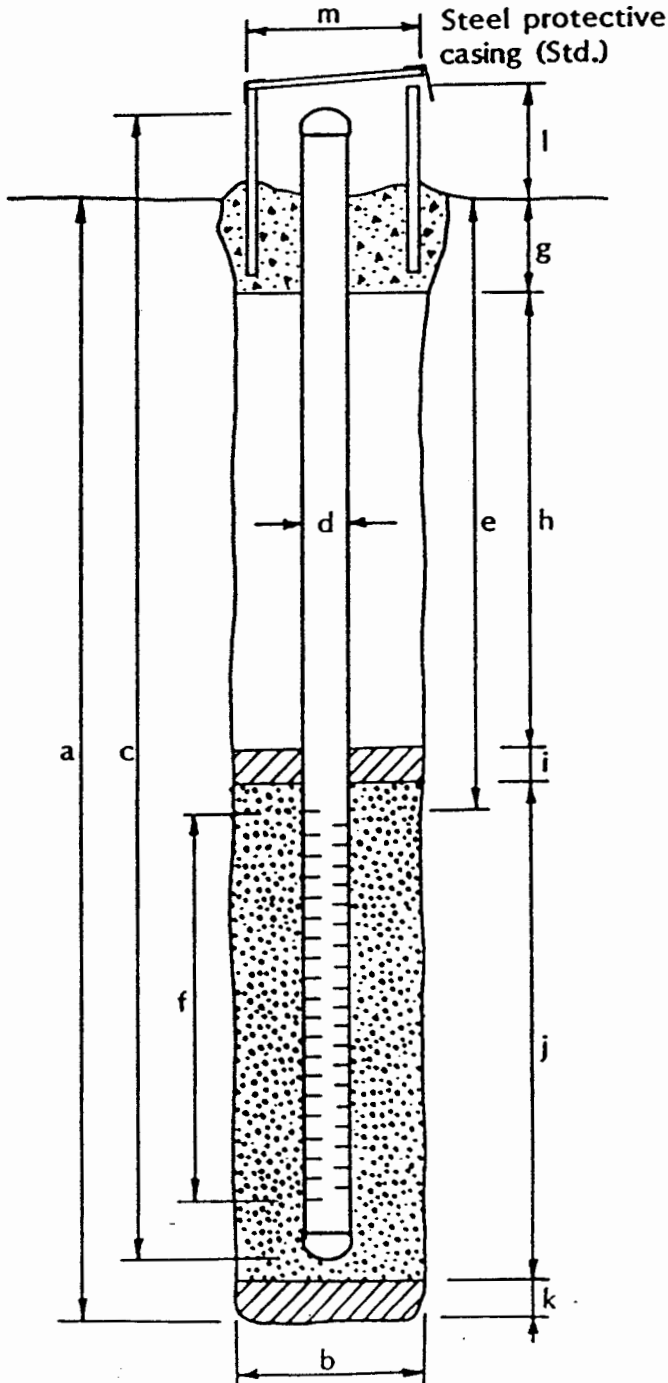
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# WELL DETAILS



PROJECT NUMBER 377-16.01  
 PROJECT NAME Signetics  
 COUNTY Bernalillo Co., NM  
 WELL PERMIT NO. N/A

BORING / WELL NO. MW-2  
 TOP OF CASING ELEV. 5159.36  
 GROUND SURFACE ELEV. 5158.15  
 DATUM Mean Sea Level



## EXPLORATORY BORING

a. Total depth 245 ft.  
 b. Diameter 7 7/8 in.  
 Drilling method Air/Mud Rotary

## WELL CONSTRUCTION

c. Casing length 240 ft.  
 Material Schedule 40 PVC  
 d. Diameter 2 in.  
 e. Depth to top perforations 200 ft.  
 f. Perforated length 30 ft.  
 Perforated interval from 200 to 230 ft.  
 Perforation type Machine Slot  
 Perforation size 0.02 inch  
 g. Surface seal 6 ft.  
 Seal material Grout w/ 3% Bentonite  
 h. Backfill 174 ft.  
 Backfill material Grout w/ 3% Bentonite  
 i. Seal 8.5 ft.  
 Seal material Volclay Bentonite  
 j. Gravel pack  $\pm$  56.5 ft.  
 Pack material CSSI 8x12 Sand  
 k. Bottom seal N/A ft.  
 Seal material N/A  
 l. Casing height \* 1.0 ft.  
 m. Protective casing diameter 10 in.  
 $\pm$  includes filter pack (.5') and natural pack (9.5')  
 \* top of PVC casing

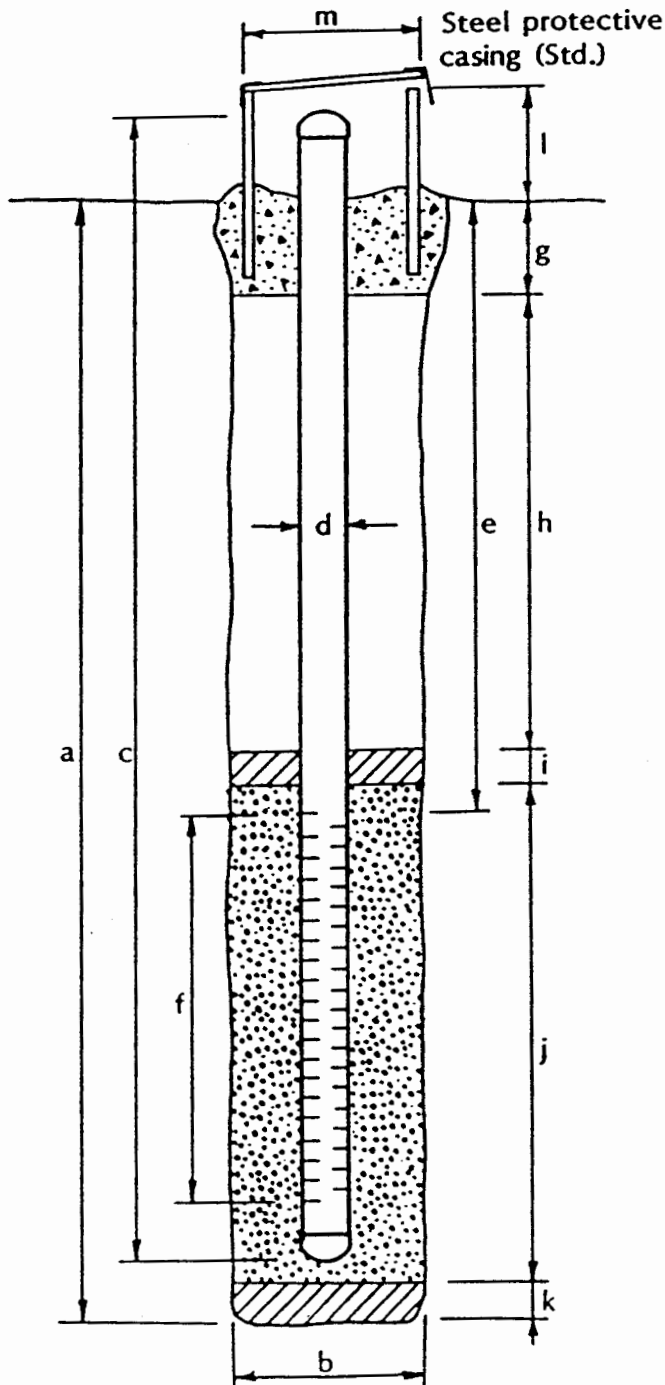
19:5

# WELL DETAILS



PROJECT NUMBER 377-16.01  
 PROJECT NAME Signetics  
 COUNTY Bernalillo Co., NM  
 WELL PERMIT NO. N/A

BORING / WELL NO. MW-3  
 TOP OF CASING ELEV. 5186.43  
 GROUND SURFACE ELEV. 5185.48  
 DATUM Mean Sea Level



## EXPLORATORY BORING

a. Total depth 260 ft.  
 b. Diameter 7 7/8 in.  
 Drilling method Air/Mud Rotary

## WELL CONSTRUCTION

c. Casing length 240.5 ft.  
 Material Schedule 40 PVC  
 d. Diameter 2 in.  
 e. Depth to top perforations 209.5 ft.  
 f. Perforated length 30 ft.  
 Perforated interval from 209.5 to 239.5 ft.  
 Perforation type Machine Slotted  
 Perforation size 0.02 inch  
 g. Surface seal 8 ft.  
 Seal material Cement w/ 3% Bentonite  
 h. Backfill 172 ft.  
 Backfill material Cement w/ 3% Bentonite  
 i. Seal 14 ft.  
 Seal material Bentonite  
 j. Gravel pack ± 66 ft.  
 Pack material CSSI 8x12 Sand  
 k. Bottom seal N/A ft.  
 Seal material N/A  
 l. Casing height \* 1.0 ft.  
 m. Protective casing diameter 10 in.

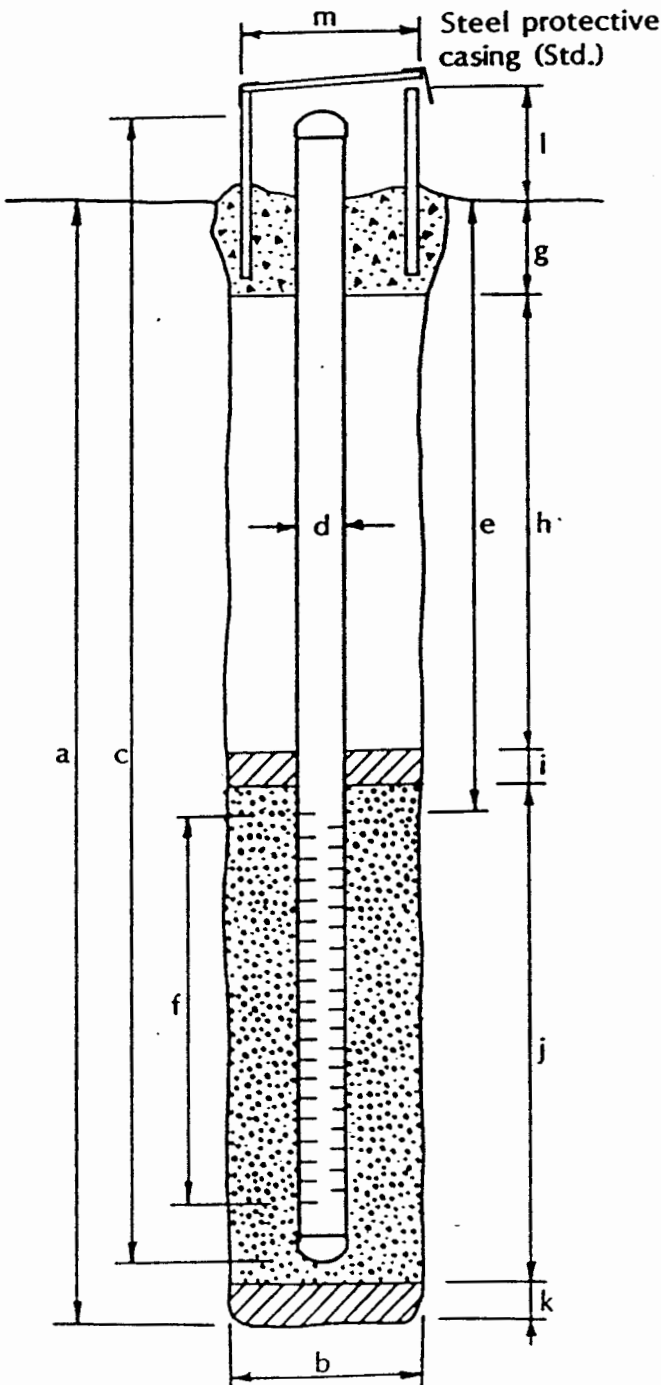
± includes filter pack (2.5 ft) and natural pack (6 ft)  
 \* top of PVC casing

# WELL DETAILS



PROJECT NUMBER 377-16.01  
 PROJECT NAME Signetics  
 COUNTY Bernalillo Co., NM  
 WELL PERMIT NO. N/A

BORING / WELL NO. MW-4  
 TOP OF CASING ELEV. 5182.94  
 GROUND SURFACE ELEV. 5182.46  
 DATUM Mean Sea Level



## EXPLORATORY BORING

- a. Total depth 260 ft.
- b. Diameter 7 7/8 in.
- Drilling method Air/Mud Rotary

## WELL CONSTRUCTION

- c. Casing length 240 ft.  
Material Schedule 40 PVC
- d. Diameter 2 in.
- e. Depth to top perforations 209.5 ft.
- f. Perforated length 30 ft.  
Perforated interval from 209.5 to 239.5 ft.  
Perforation type Machine Slotted  
Perforation size 0.02 inch
- g. Surface seal 19 ft.  
Seal material Cement w/ 3% Bentonite
- h. Backfill 169.5 ft.  
Backfill material Cement w/3% Bentonite
- i. Seal 10 ft.  
Seal material Bentonite
- j. Gravel pack<sup>±</sup> 61.5 ft.  
Pack material CSSI 8x12 Sand
- k. Bottom seal N/A ft.  
Seal material N/A
- l. Casing height\* .5 ft.
- m. Protective casing diameter 10 in.  
± includes filter pack  
\* top of PVC casing

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Table 1  
MONITORING WELL COMPLETION DETAILS

Well	Total Depth (feet)	Screened Interval (feet)	Sand Pack <sup>1</sup> Interval (feet)	Filter Pack <sup>2</sup> Interval (feet)	Seal <sup>3</sup> Interval (feet)	Backfill <sup>4</sup> Interval (feet)
MW-1	247	199.5 to 229.5	180.5 to 247.0	179.0 to 180.5	174.0 to 179.0	0 to 174.0
MW-2	245	199.5 to 229.5	189.0 to 245.0	188.5 to 189.0	180.0 to 188.5	0 to 180.0
MW-3	260	209.5 to 239.5	196.5 to 260.0	194.0 to 196.5	180.0 to 194.0	0 to 180.0
MW-4	260	209.5 to 239.5	199.5 to 260.0	198.5 to 199.5	188.5 to 198.5	0 to 188.5

1. CSSI 8x12 silica sand
2. Fine silica sand
3. Bentonite
4. Grout with 3 percent bentonite

Halogenated Volatile Organics

Method 8010

Client Name: Philips Semiconductors  
 Client ID: Trip Blank  
 Lab ID: 027075-0005-SA  
 Matrix: AQUEOUS  
 Authorized: 08 JAN 93

Sampled: 07 JAN 93  
 Prepared: NA

Received: 08 JAN 93  
 Analyzed: 20 JAN 93

Parameter	Result	Units	Reporting Limit
Chloromethane	ND	ug/L	5.0
Bromomethane	ND	ug/L	5.0
Vinyl chloride	ND	ug/L	1.0
Chloroethane	ND	ug/L	5.0
Methylene chloride	ND	ug/L	5.0
1,1-Dichloroethene	ND	ug/L	0.50
1,1-Dichloroethane	ND	ug/L	0.50
trans-1,2-Dichloroethene	ND	ug/L	0.50
Chloroform	ND	ug/L	0.50
1,1,2 Trichloro-1,2,2-trifluoroethane	ND	ug/L	1.0
1,2-Dichloroethane	ND	ug/L	1.0
1,1,1-Trichloroethane	ND	ug/L	0.50
Carbon tetrachloride	ND	ug/L	0.50
Bromodichloromethane	ND	ug/L	1.0
1,2-Dichloropropane	ND	ug/L	1.0
trans-1,3-Dichloropropene	ND	ug/L	1.0
Trichloroethene	ND	ug/L	0.50
Dibromochloromethane	ND	ug/L	1.0
cis-1,3-Dichloropropene	ND	ug/L	2.0
1,1,2-Trichloroethane	ND	ug/L	1.0
EDB (1,2-Dibromoethane)	ND	ug/L	2.0
Bromoform	ND	ug/L	5.0
1,1,2,2-Tetrachloroethane	ND	ug/L	1.0
Tetrachloroethene	ND	ug/L	0.50
Chlorobenzene	ND	ug/L	2.0

Surrogate	Recovery	
Bromochloromethane	112	%

ND = Not detected  
 NA = Not applicable

Reported By: Bret Collins

Approved By: Mark Pokorny

Halogenated Volatile Organics

Method 8010

Client Name: Philips Semiconductors  
 Client ID: Well #1  
 Lab ID: 027075-0001-SA  
 Matrix: AQUEOUS  
 Authorized: 08 JAN 93

Sampled: 06 JAN 93  
 Prepared: NA

Received: 08 JAN 93  
 Analyzed: 19 JAN 93

Parameter	Result	Units	Reporting Limit
Chloromethane	ND	ug/L	5.0
Bromomethane	ND	ug/L	5.0
Vinyl chloride	ND	ug/L	1.0
Chloroethane	ND	ug/L	5.0
Methylene chloride	ND	ug/L	5.0
1,1-Dichloroethene	ND	ug/L	0.50
1,1-Dichloroethane	ND	ug/L	0.50
trans-1,2-Dichloroethene	ND	ug/L	0.50
Chloroform	ND	ug/L	0.50
1,1,2 Trichloro-1,2,2-trifluoroethane	ND	ug/L	1.0
1,2-Dichloroethane	ND	ug/L	1.0
1,1,1-Trichloroethane	ND	ug/L	0.50
Carbon tetrachloride	ND	ug/L	0.50
Bromodichloromethane	ND	ug/L	1.0
1,2-Dichloropropane	ND	ug/L	1.0
trans-1,3-Dichloropropene	ND	ug/L	1.0
Trichloroethene	ND	ug/L	0.50
Dibromochloromethane	ND	ug/L	1.0
cis-1,3-Dichloropropene	ND	ug/L	2.0
1,1,2-Trichloroethane	ND	ug/L	1.0
EDB (1,2-Dibromoethane)	ND	ug/L	2.0
Bromoform	ND	ug/L	5.0
1,1,2,2-Tetrachloroethane	ND	ug/L	1.0
Tetrachloroethene	6.2	ug/L	0.50
Chlorobenzene	ND	ug/L	2.0
Surrogate	Recovery		
Bromochloromethane	124	%	

ND = Not detected  
 NA = Not applicable

Reported By: Bret Collins

Approved By: Mark Pokorny



Halogenated Volatile Organics

Method 8010

Client Name: Philips Semiconductors  
 Client ID: Well #2  
 Lab ID: 027075-0002-SA  
 Matrix: AQUEOUS  
 Authorized: 08 JAN 93

Sampled: 06 JAN 93  
 Prepared: NA

Received: 08 JAN 93  
 Analyzed: 19 JAN 93

Parameter	Result	Units	Reporting Limit
Chloromethane	ND	ug/L	5.0
Bromomethane	ND	ug/L	5.0
Vinyl chloride	ND	ug/L	1.0
Chloroethane	ND	ug/L	5.0
Methylene chloride	ND	ug/L	5.0
1,1-Dichloroethene	ND	ug/L	0.50
1,1-Dichloroethane	ND	ug/L	0.50
trans-1,2-Dichloroethene	ND	ug/L	0.50
Chloroform	ND	ug/L	0.50
1,1,2 Trichloro-1,2,2-trifluoroethane	ND	ug/L	1.0
1,2-Dichloroethane	ND	ug/L	1.0
1,1,1-Trichloroethane	ND	ug/L	0.50
Carbon tetrachloride	ND	ug/L	0.50
Bromodichloromethane	ND	ug/L	1.0
1,2-Dichloropropane	ND	ug/L	1.0
trans-1,3-Dichloropropene	ND	ug/L	1.0
Trichloroethene	ND	ug/L	0.50
Dibromochloromethane	ND	ug/L	1.0
cis-1,3-Dichloropropene	ND	ug/L	2.0
1,1,2-Trichloroethane	ND	ug/L	1.0
EDB (1,2-Dibromoethane)	ND	ug/L	2.0
Bromoform	ND	ug/L	5.0
1,1,2,2-Tetrachloroethane	ND	ug/L	1.0
Tetrachloroethene	7.1	ug/L	0.50
Chlorobenzene	ND	ug/L	2.0
Surrogate	Recovery		
Bromochloromethane	110	%	

ND = Not detected  
 NA = Not applicable

Reported By: Bret Collins

Approved By: Mark Pokorny

Halogenated Volatile Organics

Method 8010

Client Name: Philips Semiconductors  
 Client ID: Well #3  
 Lab ID: 027075-0003-SA  
 Matrix: AQUEOUS  
 Authorized: 08 JAN 93

Sampled: 07 JAN 93  
 Prepared: NA

Received: 08 JAN 93  
 Analyzed: 19 JAN 93

Parameter	Result	Units	Reporting Limit
Chloromethane	ND	ug/L	5.0
Bromomethane	ND	ug/L	5.0
Vinyl chloride	ND	ug/L	1.0
Chloroethane	ND	ug/L	5.0
Methylene chloride	ND	ug/L	5.0
1,1-Dichloroethene	ND	ug/L	0.50
1,1-Dichloroethane	ND	ug/L	0.50
trans-1,2-Dichloroethene	ND	ug/L	0.50
Chloroform	ND	ug/L	0.50
1,1,2 Trichloro-1,2,2-trifluoroethane	ND	ug/L	1.0
1,2-Dichloroethane	ND	ug/L	1.0
1,1,1-Trichloroethane	ND	ug/L	0.50
Carbon tetrachloride	ND	ug/L	0.50
Bromodichloromethane	ND	ug/L	1.0
1,2-Dichloropropane	ND	ug/L	1.0
trans-1,3-Dichloropropene	ND	ug/L	1.0
Trichloroethene	ND	ug/L	0.50
Dibromochloromethane	ND	ug/L	1.0
cis-1,3-Dichloropropene	ND	ug/L	2.0
1,1,2-Trichloroethane	ND	ug/L	1.0
EDB (1,2-Dibromoethane)	ND	ug/L	2.0
Bromoform	ND	ug/L	5.0
1,1,2,2-Tetrachloroethane	ND	ug/L	1.0
Tetrachloroethene	ND	ug/L	0.50
Chlorobenzene	ND	ug/L	2.0
Surrogate	Recovery		
Bromochloromethane	100	%	

ND = Not detected  
 NA = Not applicable

Reported By: Bret Collins

Approved By: Mark Pokorny

Halogenated Volatile Organics

Method 8010

Client Name: Philips Semiconductors  
 Client ID: Well #4  
 Lab ID: 027075-0004-SA  
 Matrix: AQUEOUS  
 Authorized: 08 JAN 93

Sampled: 07 JAN 93  
 Prepared: NA

Received: 08 JAN 93  
 Analyzed: 20 JAN 93

Parameter	Result	Units	Reporting Limit
Chloromethane	ND	ug/L	5.0
Bromomethane	ND	ug/L	5.0
Vinyl chloride	ND	ug/L	1.0
Chloroethane	ND	ug/L	5.0
Methylene chloride	ND	ug/L	5.0
1,1-Dichloroethene	ND	ug/L	0.50
1,1-Dichloroethane	ND	ug/L	0.50
trans-1,2-Dichloroethene	ND	ug/L	0.50
Chloroform	ND	ug/L	0.50
1,1,2 Trichloro-1,2,2-trifluoroethane	ND	ug/L	1.0
1,2-Dichloroethane	ND	ug/L	1.0
1,1,1-Trichloroethane	ND	ug/L	0.50
Carbon tetrachloride	ND	ug/L	0.50
Bromodichloromethane	ND	ug/L	1.0
1,2-Dichloropropane	ND	ug/L	1.0
trans-1,3-Dichloropropene	ND	ug/L	1.0
Trichloroethene	ND	ug/L	0.50
Dibromochloromethane	ND	ug/L	1.0
cis-1,3-Dichloropropene	ND	ug/L	2.0
1,1,2-Trichloroethane	ND	ug/L	1.0
EDB (1,2-Dibromoethane)	ND	ug/L	2.0
Bromoform	ND	ug/L	5.0
1,1,2,2-Tetrachloroethane	ND	ug/L	1.0
Tetrachloroethene	5.4	ug/L	0.50
Chlorobenzene	ND	ug/L	2.0
Surrogate	Recovery		
Bromochloromethane	108	%	

ND = Not detected  
 NA = Not applicable

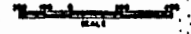
Reported By: Bret Collins

Approved By: Mark Pokorny

LIQUID WASTE/GROUND WATER  
SURVEILLANCE

OCT 27 1986

RECEIVED



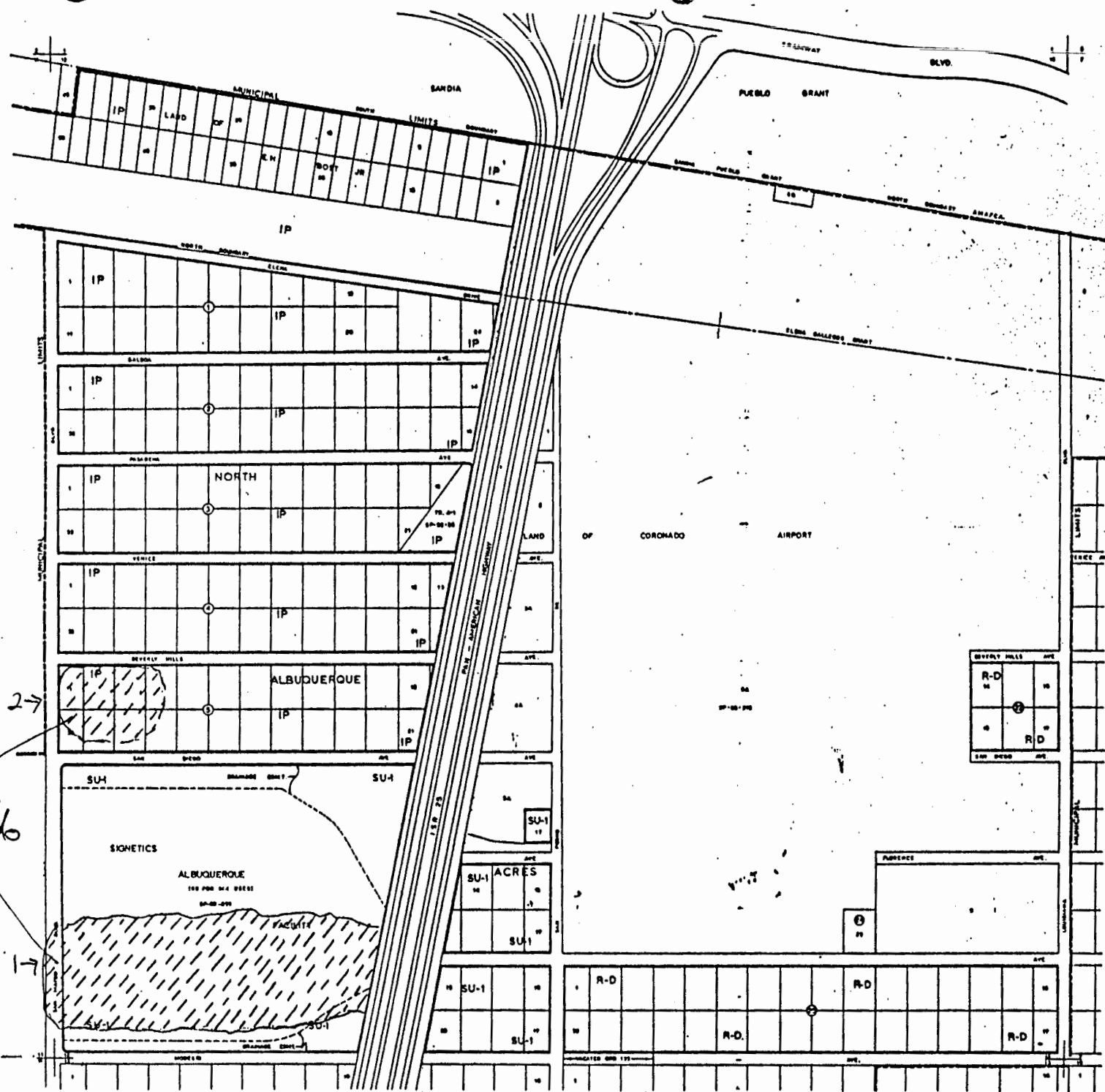
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T 11 N  
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SEC. 10

OFFICIAL PROPERTY CODE  
1-04-000

MAP SHEETS THROUGH  
MARCH 1980

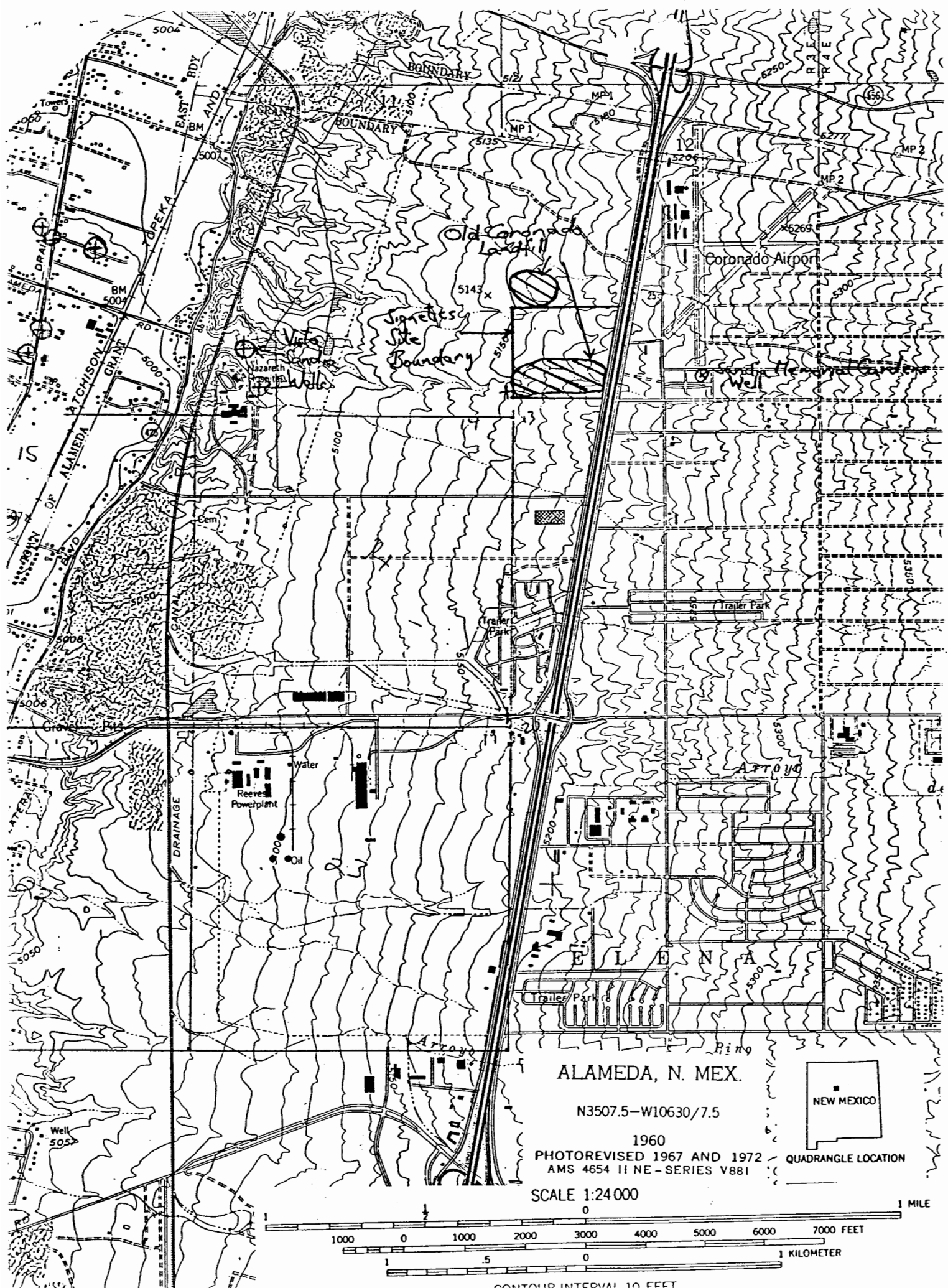
**B-18-Z**

(17) OF 14 BOUNDARY  
PLANS IN SET (12)



2 -> Old coronado  
roadfill

1 ->



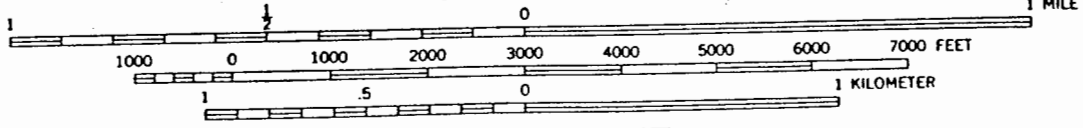
ALAMEDA, N. MEX.

N3507.5-W10630/7.5

1960  
 PHOTOREVISED 1967 AND 1972  
 AMS 4654 II NE-SERIES V881



SCALE 1:24 000



CONTOUR INTERVAL 10 FEET

Table 1  
MONITORING WELL COMPLETION DETAILS

Well	Total Depth (feet)	Screened Interval (feet)	Sand Pack <sup>1</sup> Interval (feet)	Filter Pack <sup>2</sup> Interval (feet)	Seal <sup>3</sup> Interval (feet)	Backfill <sup>4</sup> Interval (feet)
MW-1	247	199.5 to 229.5	180.5 to 247.0	179.0 to 180.5	174.0 to 179.0	0 to 174.0
MW-2	245	199.5 to 229.5	189.0 to 245.0	188.5 to 189.0	180.0 to 188.5	0 to 180.0
MW-3	260	209.5 to 239.5	196.5 to 260.0	194.0 to 196.5	180.0 to 194.0	0 to 180.0
MW-4	260	209.5 to 239.5	199.5 to 260.0	198.5 to 199.5	188.5 to 198.5	0 to 188.5

1. CSSI 8x12 silica sand
2. Fine silica sand
3. Bentonite
4. Grout with 3 percent bentonite